What is claimed is:

1. A photoimageable composition comprising:

i) a photoactive component;

ii) a component that that comprises one or more Si atoms; and

iii) a component that comprises one or more sulfonamide groups.

2. The photoimageable composition of claim 1 wherein a single component comprises both one or more Si atoms and one or more sulfonamide groups.

3. The photoimageable composition of claim 1 wherein the photoimageable composition comprises a polymer that comprises both one or more Si atoms and one or more sulfonamide groups.

4. The photoimageable composition of claim 3 wherein the polymer further comprises photoacid-labile groups.

5. The photoimageable composition of claim 4 wherein the photoacid-labile groups are ester groups or acetal groups.

6. The photoimageable composition of claim 3 wherein the polymer comprises aromatic groups.

7. The photoimageable composition of claim 3 wherein the polymer comprises phenyl groups.

8. The photoimageable composition of claim 3 wherein the polymer is substantially free of aromatic groups.

9. The photoimageable composition of claim 1 wherein the photoimageable composition comprises a polymer that contains one or more Si atoms and a distinct component that comprises one or more sulfonamide groups.

10. The photoimageable composition of claim 9 wherein the photoimageable composition comprises a polymer that contains one or more Si atoms and a distinct polymer that comprises one or more sulfonamide groups.

11. The photoimageable composition of claim 1 wherein the composition comprises a polymer that has one or more Si atoms and one or more aqueous base-solubilizing groups.

12. The photoimageable composition of claim 11 wherein aqueous solubilizing groups are fluorinated alcohols, carboxylic acid and/or thiols.

13. The photoimageable composition of claim 1 wherein the composition comprises a polymer that comprises at least three distinct repeat units.

14. The photoimageable composition of claim 1 wherein the composition is a chemically-amplified positive acting photoresist.

15. The photoimageable composition of claim 1 further comprising a crosslinker component.

16. The photoimageable composition of claim 1 wherein the composition is a negative-acting photoresist.

17. A coated substrate comprising:

a) a polymer composition coating layer applied over a substrate surface;

b) a coating layer of a photoimageable composition of claim 1 disposed above the polymer composition coating layer.

18. A coated substrate of claim 17 wherein the polymer composition comprises a phenolic resin.

19. A method for forming a electronic device, comprising:

(a) applying on a substrate a coating layer of a polymer composition;

(b) above the polymer composition coating layer, applying a photoimageable composition of claim 1;

(c) exposing the photoimageable composition coating layer to activating radiation and developing the exposed photoimageable layer.

20. An article of manufacture comprising a substrate comprising a coating layer of a photoimageable composition of claim 1.

21. A photoresist composition comprising a photoactive component and a resin that comprises one or more Si atoms and one or more sulfonamide groups.

22. The photoresist composition of claim 21 wherein the resin is a silsesquioxane.

23. A coated substrate comprising:

a) an organic polymer composition coating layer applied over a substrate surface;

b) a coating layer of a photoresist composition of claim 21 disposed above the polymer composition coating layer.